

## Improved Charge Transfer and Barrier Lowering across a Au–MoS<sub>2</sub> Interface through Insertion of a Layered Ca<sub>2</sub>N Electride

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Transition-metal dichalcogenides (TMDCs) are a family of layered semiconductors that offer great potential in the upcoming field of two-dimensional (2D) electronics. In particular, MoS<sub>2</sub> is a TMDC with a desirable band gap for the construction of transistors, solar cells, and biochemical sensors. However, MoS<sub>2</sub> layers lack any dangling out-of-plane bonds, making it challenging to form the proper electrical contacts required in any practical device. In this talk, I will discuss how the insertion of a 2D layered electride like Ca<sub>2</sub>N, an electron-rich material, at a metal-MoS<sub>2</sub> interface may remedy this problem. As a proof-of-concept, we study a Au-Ca<sub>2</sub>N-MoS<sub>2</sub> heterostructure within a density-functional theory (DFT) framework using the exchange-hole dipole moment (XDM) dispersion model. We choose Au since it is a common contact metal, its interface with MoS<sub>2</sub> is well characterised, and it exhibits strong Fermi-level pinning, as well as high Schottky and tunneling barriers. The insertion of Ca<sub>2</sub>N eliminates both the tunneling and Schottky barriers through nearly complete charge transfer from the electride surface states. The resulting Au-Ca<sub>2</sub>N-MoS<sub>2</sub> heterostructure shows features of a true ohmic contact. Our promising results may indicate that the insertion of an electride may solve the more general metal-TMDC contact problem.